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D2S EXPANDS GPGPU ACCELERATION CAPABILITY FOR ADVANCED SEMICONDUCTOR LITHOGRAPHY AND PHOTOMASK MANUFACTURING WITH ACQUISITION OF GAUDA

SAN JOSE, Calif., June 3, 2014—D2S®, a supplier of computational design platforms based on eBeam and general purpose graphic processing unit (GPGPU) technologies, today announced that it has acquired all assets of Gauda, Inc., a developer of GPGPU-based computational lithography acceleration technology headquartered in Sunnyvale, Calif. The acquisition, which includes all of Gauda’s patents related to GPGPU acceleration as well as software, will strengthen D2S’ capabilities in software for semiconductor manufacturing, including the increasingly critical area of wafer plane analysis—which evaluates how accurately complex shapes on advanced photomasks print as predicted on the wafer.

“The feedback that we’ve received from customers and partners has indicated that GPGPU acceleration will be increasingly critical to enable more accurate photomask writing and higher-yielding wafer lithography processes,” stated Aki Fujimura, CEO of D2S. “The acquisition of Gauda provides important technology and intellectual property that will help extend the capabilities of our TrueMask product family and bolster our GPGPU offerings.”

About D2S, Inc.

D2S is a supplier of a computational design platform to maximize eBeam technology to reduce mask costs for both low- and high-volume applications. D2S TrueMask® solutions enable advanced photomask designs at 28-nm-and-below process nodes using complex shapes for superior wafer quality but within practical, cost-effective write-times using eBeam mask writing equipment. D2S is the managing sponsor of the eBeam Initiative. Headquartered in San Jose, Calif., the company was founded in 2007. For more information, see: www.design2silicon.com.

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